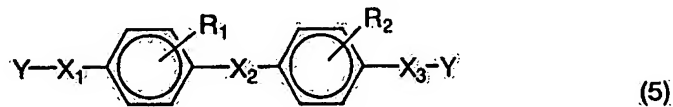


Amendments to the Claims:

Please cancel Claims 1 – 14.

15. (Original) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being an oligomer represented by the following formula (5):



wherein R<sub>1</sub> and R<sub>2</sub> may be the same as or different from each other, and denote hydrogen, halogen, an alkyl group, an alkoxy group or a trifluoromethyl group; X<sub>1</sub>, X<sub>2</sub> and X<sub>3</sub> may be the same as or different from each other, and denote a connecting group including at least one selected from the group consisting of an alkylene, alyleneoxy, oxyalkylene and aromatic group; and Y denotes a polymerization activating group.

16. (Original) A method of producing said photosensitive composition for optical waveguides as claimed in Claim 15, said method comprising the steps of:

heating a silicone oligomer in the presence of a solid catalyst; and

filtering said solid catalyst, concentrating filtrate, and further adding a polymerization initiator.

17. (Original) A method of forming a polymer optical waveguide pattern, comprising the steps of:

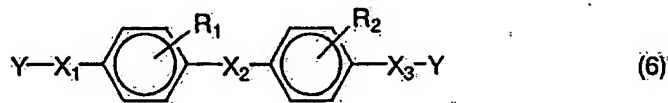
applying and drying a photosensitive composition for optical waveguides;

irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 15 is used as said photosensitive composition for optical waveguides.

18. (Original) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being an oligomer represented by the following formula (6):



wherein R<sub>1</sub> and R<sub>2</sub> may be the same as or different from each other, and denote hydrogen, halogen, an alkyl group, an alkoxy group or a trifluoromethyl group; X<sub>1</sub>, X<sub>2</sub> and X<sub>3</sub> may be the same as or different from each other, and denote a connection group including at least one selected from the group consisting of an alkylene, alkyleneoxy, oxyalkylene and aromatic group, and including at least one OH group; and Y denotes a polymerization activating group.

19. (Original) A method of producing the photosensitive composition for optical waveguides as claimed in Claim 18, said method comprising the steps of:

heating a silicone oligomer in the presence of a solid catalyst; and

filtering said solid catalyst, concentrating filtrate, and further adding a polymerization initiator.

20. (Original) A method of forming a polymer optical waveguide pattern, comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;

irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 18 is used as said photosensitive composition for optical waveguides.